



AC PLASMA SOURCE G GK-LF 500

Our long term experience in the vacuum and related technology fields allowed to develop a product line of electronic instruments such as Plasma Source Generators and Matching Networks. These products have been created by the deep experience and knowledge of Plasma inside our technical department which lead to the realization of user-friendly, reliable and advanced solutions.



This is an AC source with 50Khz frequency for plasma applications, at low cost and very compact. The system provided includes the adaptation transformer with 3 taps, user-selectable and complete with measuring circuits.

The GGK-LF-500 is available in two version, one with display and control unit endbedded, the second one is available in a black box version suitable to who prefer control the unit trough PC or PLC trough RS-232 communication, is also possible connect the black box unit to our remote handled controller unit.

The system provides 500 watt at 50 Khz, and the impedance matching is possible from 150 to 2500 ohm, by selecting one of the 3 possible configurations for the output transformer.

Fields of use

Production of PVD and PECVD reactors
Research & Development

Main Applications

Glow discharge (instead of using conventional DC generator)
PECVD deposition process
Generator for small sputtering cathodes
BIAS source for ICP system
Cleaning and activation process via plasma.

TECHNICAL SPECIFICATIONS

Dimensions	Very compact : 340Dx150Wx120H mm. weight about 2 kg
Connection	Direct electrode connection. No matching network required
Power	Full power of 500Watt available over an impedance range of 3 to 1 without transformer tap adjustment.
Measurement system	Full, accurate measurement built-in system: RMS voltage, DC self bias, power readings available on user port.
Arc detection	Active arc detection and quencing.
Efficiency	Very high >90% no forced cooling required.
Protection	Complete protection circuit: Overtemperature, overvoltage, output power limiting.

